#### **Tritium on Metal Surfaces**



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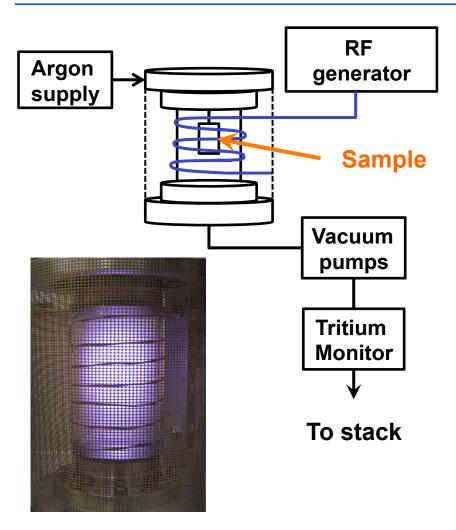
#### **Summary/Conclusions**



- Tritium concentrates in the water layers covering metal surfaces
- Water layers on the surface 'pump' tritium from the metal bulk
- The relative removal rate of tritium from the surface does not depend on
  - the initial tritium loading pressure at room temperature,
  - the storage time in an inert environment, or
  - the metal type
- Regrowth of surface activity is:
  - rapid, and
  - controlled by diffusion from the 'near-surface' bulk



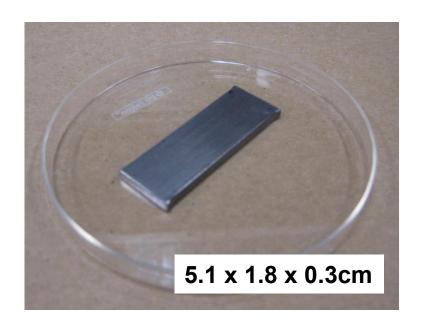
# An argon plasma generated by a radio-frequency (RF) field was used to desorb tritium from metals into a flowing gas stream ...



- Plasma was ignited in argon by passing a 13.56 MHz AC current through a copper coil
- Sample floated at the plasma potential
  - ionic flux = electron flux
- Tritium released from the sample was purged into a downstream inline tritium monitor
- Base pressure ≈ 10<sup>-4</sup> Torr
  - Trace water in vacuum system re-deposits on metal surface within 15 sec



### Metallic samples were de-greased, stored in hard vacuum for 24 hours, then charged with DT gas at room temperature



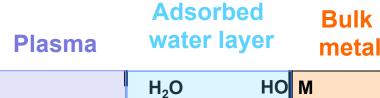
- Samples were separated from each other during the DT loading
- Samples stored under -50°C DP helium until experiment
- Batch #1 stored in same container& removed using a glove-bag
- Batch #2 stored in separate containers

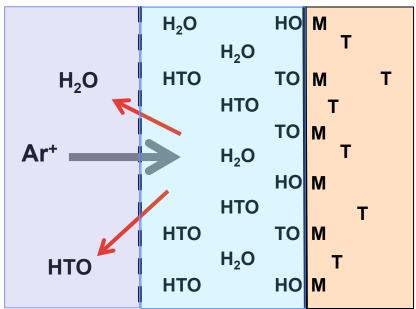
Batch Number	Time (hrs)	Pressure (Torr)	Isotopic Ratio (%)	Storage time
1	3	687	45%	3.5 years
2	24	659	39%	36 days



#### Water was removed from the sample surface using a series of 2second plasma bursts





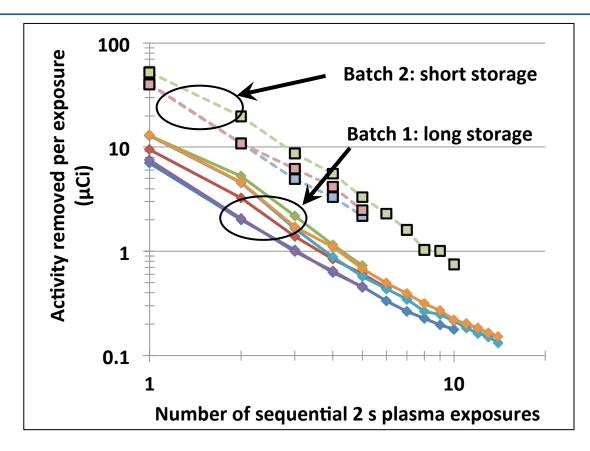


- Metal surface comprises:
  - Hydroxyl layer
  - Proton bonded 'ice' layer
  - Mobile Van der Waal bonded water
- Adsorbed water layer regrows between exposures
- Tritium migrates into freshly formed tritium-free water layer



# Initial activity on the stainless steel samples determines the amount of activity removed during each following exposure

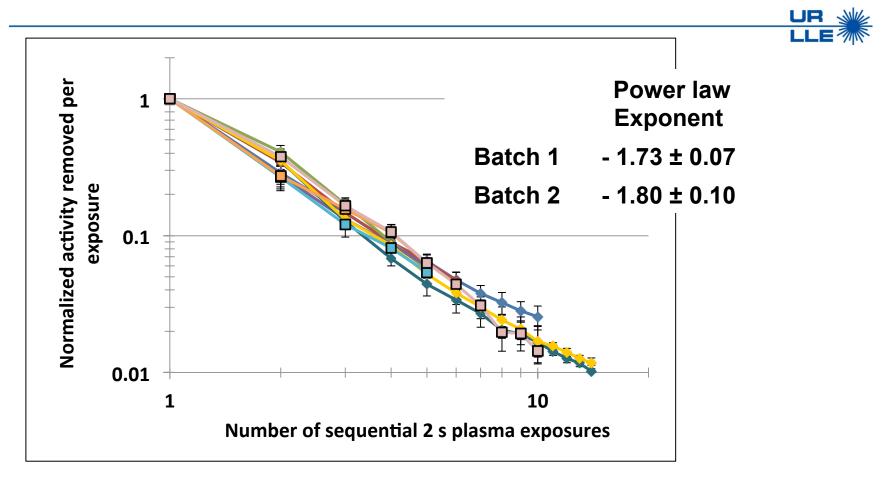




Batch 2 samples contain more activity: Shorter storage & longer loading time



#### Trend in activity removed does not depend on sample history

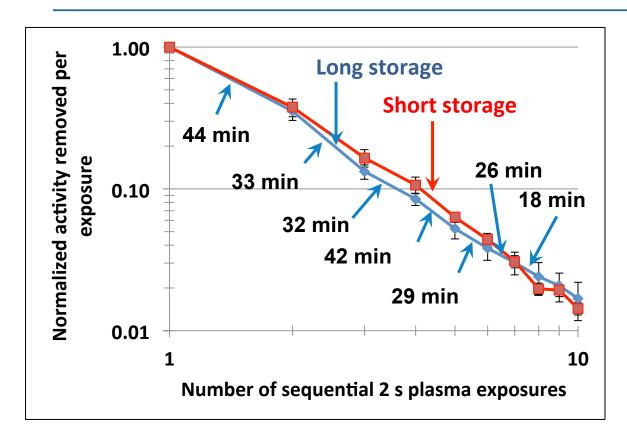


- Data were normalized to the initial amount removed
- Trend fitted to a power law



### The trend in activity removed does not depend on dwell period between plasma shots



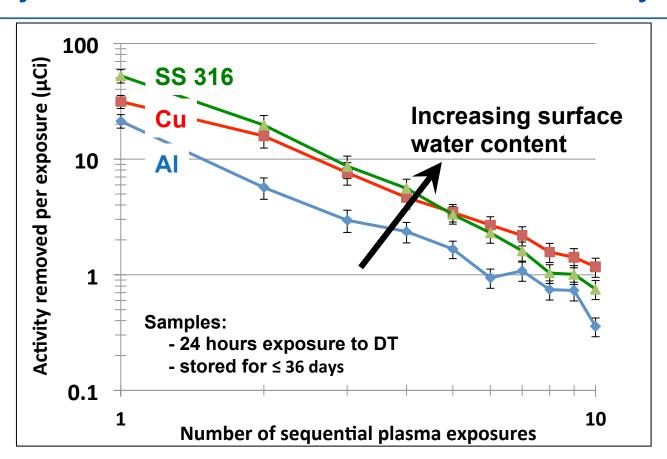


- Dwell times for "Short storage" samples were fixed at 20 min between shots
- Dwell times for "Long storage" samples were varied

Adjusting the dwell times between 18 and 44 min does not change the relative amount of activity removed from the metal



### Total removable surface activity increases with the number of monolayers of adsorbed water at a fixed relative humidity



#### Water isotherm references

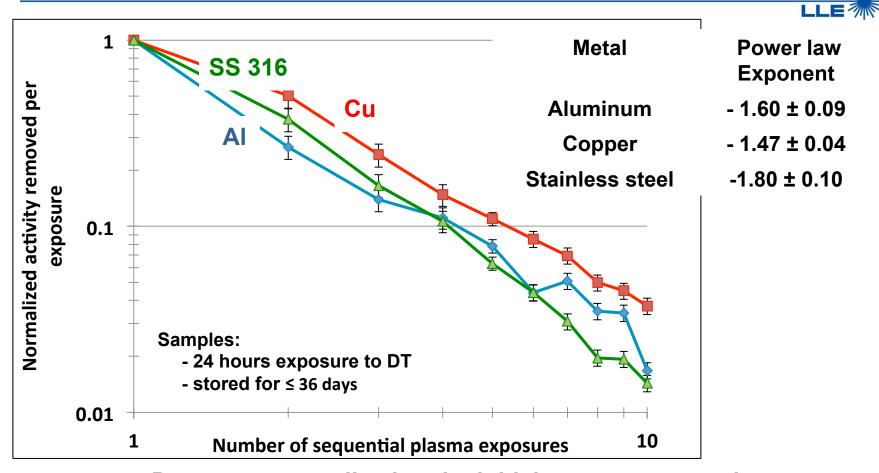
Aluminum: Al-Abadleh, H.A, et al.; Langmuir, 19, 2003, p. 341

Copper: Sharma, S.P.; J. Vac. Sci. Tech. 16(5), 1979, p. 1557

Stainless steel: Ohmi, T. et al.; Rev. Sci. Instrum., 64(9), 1993, p. 2683



# Activity removal from stainless steel, copper, and aluminum appears to follow the same trend for the three metals



- Data were normalized to the initial amount removed
- Trend fitted to a power law

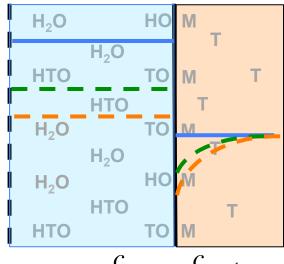


# A model based on Fickian diffusion of atomic hydrogen through two metallurgically bonded media explains the data





#### Bulk metal



$$\frac{c_{water}}{S_{water}} = \frac{c_{metal}}{S_{metal}}$$

#### **Assumptions:**

- Constant chemical potential across the boundary
- Rapid diffusivity through the oxide into the water layer
- Tritium migration across metal/oxide boundary limited by metal diffusivity
- No tritium loss from sample in storage

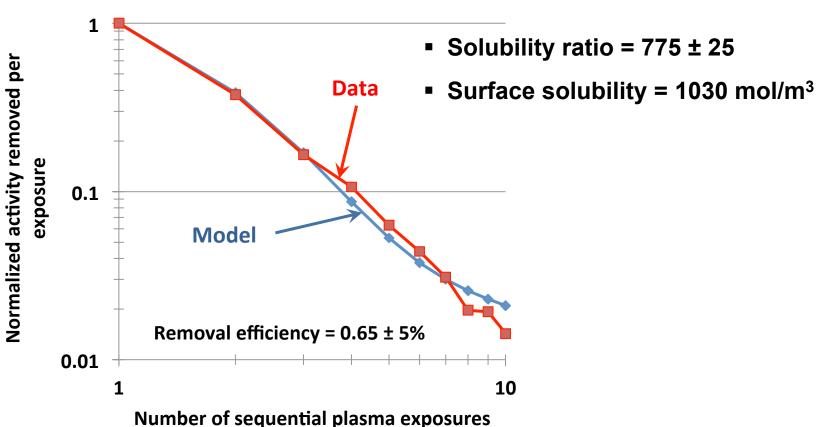
Equilibrium

Response to 'T' empty water layer



# Less than 1% of surface sites on stainless steel are occupied following an exposure to tritium gas at room temperature

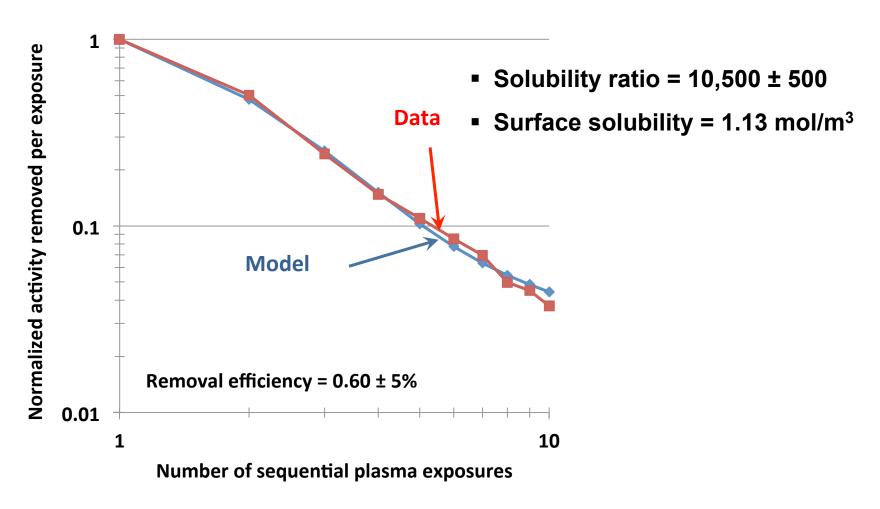






# Less than 10<sup>-3</sup>% of surface sites on copper are occupied following an exposure to tritium gas at room temperature

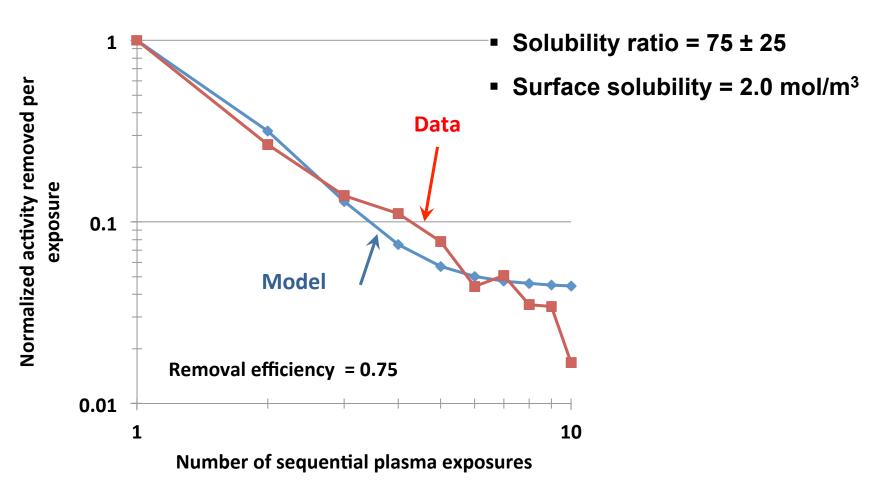






# Less than 10<sup>-2</sup>% of surface sites on aluminum are occupied following an exposure to tritium gas at room temperature







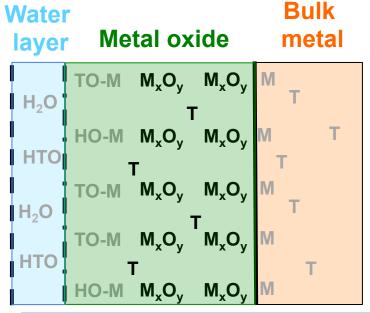
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### Including the thickness of metal-oxides on metals leads to similar solubilities for tritium on the surface of simple metals: Cu & Al\_



- Metal-oxide thicknesses grown at room temperature are metal dependent and less soluble than adsorbed water layer
- Surface solubility of Al and Cu including their metal-oxide layers are similar
- Solubility on steel remains high due to complex surface??

RH ~ 0%			Surface Solubility (mol/m³)	
Metal	Adsorbed water (nm)	Metal-oxide (nm)	Without oxide	With oxide
Al	0.3	1.0	$(4.6 \pm 0.3) \times 10^4$	$2.0 \pm 0.7$
Cu	0.3	9.5	36 ± 1	1.1 ± 0.1
SS	0.7	12.0	$(6.2 \pm 0.1) \times 10^3$	1030 ± 30

